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(54) **DISPLAY SUBSTRATE, MANUFACTURING METHOD THEREOF AND DISPLAY APPARATUS**

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(57) **ABSTRACT**

Display substrate, manufacturing method thereof and display apparatus are provided. The display substrate includes display and periphery areas, and further includes: first and second signal lines, first and second planarization layers, where each of first and second signal lines is located at periphery area, and includes portion extending in first direction; at least part of first signal line is located between display area and second signal line, first spacing region is provided between projection of first signal line onto base of display substrate and projection of second signal line onto base; first planarization portion including first planarization portion located at periphery area; second planarization layer including first via hole, projection of which onto base overlaps with first spacing region at first overlap region; and projection of first planarization portion onto base overlaps with first overlap region at second overlap region.

